

Title (en)

Light-sensitive silver halide photographic material, silver halide emulsion, and process for preparing these.

Title (de)

Photographisches, lichtempfindliches Silberhalogenidmaterial, Silberhalogenidemulsion, und Verfahren zu ihrer Herstellung.

Title (fr)

Matériaux photographiques à l'halogénure d'argent sensible à la lumière, émulsion à l'halogénure d'argent, et procédé pour leur préparation.

Publication

**EP 0421426 A1 19910410 (EN)**

Application

**EP 90119057 A 19901004**

Priority

JP 25931089 A 19891003

Abstract (en)

A light sensitive silver halide photographic material having at least one of the silver halide emulsion layers which comprises a silver halide emulsion mainly composed of twinned crystal grains and having a proportion of not more than 1/20 for a number of fogging grains to a number of total silver halide grains in the layer is disclosed. A method of preparing the silver halide emulsion is also disclosed. In the preparation process, a silver compound is added under conditions of a pH of from 1 to 5 in respect of not less than 50 mol % of residual silver compound added in a course of formation of silver halide grains, after at least 90 mol % of silver compound has been added.

IPC 1-7

**G03C 1/015; G03C 1/035**

IPC 8 full level

**G03C 1/005** (2006.01); **G03C 1/035** (2006.01); **G03C 7/30** (2006.01)

CPC (source: EP)

**G03C 1/0051** (2013.01); **G03C 7/3022** (2013.01)

Citation (search report)

- EP 0273411 A2 19880706 - FUJI PHOTO FILM CO LTD [JP]
- US 2996382 A 19610815 - LUCKEY GEORGE W, et al
- JP S6114630 A 19860122 - KONISHIROKU PHOTO IND
- [Y] PATENT ABSTRACTS OF JAPAN vol. 10, no. 7 (P-419)(2064) 11 January 1986, & JP-A-60 164738 (KONISHIROKU) 27 August 1985,
- [Y] PHOTOGRAPHIC SCIENCE AND ENGINEERING. vol. 5, no. 6, November 1961, WASHINGTON US pages 332 - 336; C.R.Berry et al.: "Effects of environment on the Growth of Silver Bromide Microcrystals"
- [YD] RESEARCH DISCLOSURE. no. 299, March 1989, HAVANT GB pages 185 - 197; "Nucleation of Tabular Grain Emulsions at High pBr"

Cited by

US5310644A

Designated contracting state (EPC)

DE GB IT NL

DOCDB simple family (publication)

**EP 0421426 A1 19910410**; JP H03219230 A 19910926

DOCDB simple family (application)

**EP 90119057 A 19901004**; JP 25931089 A 19891003